Docket No.

197802US2S

### IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF:

Wakako MORIYAMA, et al.

**SERIAL NO:** 

**New Application** 

GAU:

FILED:

Herewith

**EXAMINER:** 

FOR:

METHOD FOR MANUFACTURING SEMICONDUCTOR DEVICES USING THERMAL NITRIDE FILMS AS GATE

**INSULATING FILMS** 

## **INFORMATION DISCLOSURE STATEMENT UNDER 37 CFR 1.97**

ASSISTANT COMMISSIONER FOR PATENTS WASHINGTON, D.C. 20231

SIR:

Applicant(s) wish to disclose the following information.

#### REFERENCES

- The applicant(s) wish to make of record the references listed on the attached form PTO-1449. Copies of the listed references are attached, where required, as are either statements of relevancy or any readily available English translations of pertinent portions of any non-English language references.
- ☐ A check is attached in the amount required under 37 CFR §1.17(p).

#### **RELATED CASES**

- Attached is a list of applicant's pending application(s) or issued patent(s) which may be related to the present application. A copy of the patent(s) is attached along with PTO 1449.
- ☐ A check is attached in the amount required under 37 CFR §1.17(p).

#### CERTIFICATION

- Each item of information contained in this information disclosure statement was cited in a communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of this statement.
- □ No item of information contained in this information disclosure statement was cited in a communication from a foreign patent office in a counterpart foreign application or, to the knowledge of the undersigned, having made reasonable inquiry, was known to any individual designated in 37 CFR §1.56(c) more than three months prior to the filing of this statement.

#### **PETITION**

Applicant(s) hereby request consideration of the attached information. A check is attached in the amount of the Petition fee required under 37 CFR §1.17(i)(1).

## DEPOSIT ACCOUNT

Please charge any additional fees for the papers being filed herewith and for which no check is enclosed herewith, or credit any overpayment to deposit account number 15-0030. A duplicate copy of this sheet is enclosed.

Respectfully submitted,

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# LIST OF RELATED CASES

Docket Number	Serial or Patent No.	Filing or Issue Date	Status or Patentee
PER CLIENT	09/106,208	06/29/98	UNKNOWN
PER CLIENT	09/559,757	04/27/00	UNKNOWN



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## **STATEMENT OF RELEVANCY**

Reference AO (11-154711) on Form PTO-1449.

This reference shows that the corner of a gate electrode is rounded by an oxidation process.

Reference AP (2000-12710) on Form PTO-1449.

This reference mentions that a bird's beak is suppressed in the film containing nitrogen.